

Notice of References Cited	Application/Control No. 10/706,757		Applicant(s)/Patent Under Reexamination CHOU ET AL.	
	Examiner Binh X. Tran		Art Unit 1713	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2002/0102490	08-2002	Ito et al.	430/270.1
*	C	US-5,981,616	11-1999	Yamamura et al.	522/168
*	D	US-5,866,294	02-1999	Oguni et al.	430/166
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NON-PATENT DOCUMENTS

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	U	Chou, Krauss and Renstrom, "Nanoimprint lithography", Journal Vacuum Science Technology B 14 (6); pages 4129-4133; 1996
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.